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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors: HAMAMATSU, et al

U.S. Patent No.: 7,187,438

Issued: March 6, 2007

For: APPARATUS AND METHOD FOR INSPECTING DEFECTS

REQUEST FOR CERTIFICATE OF CORRECTION
UNDER 37 CFR 1.322

Mail Stop: Cert. of Correction (No Fee)
Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

June 21, 2007

Certificate
JUN 26 2007
of Correction

Sir:

In the above-identified patent, it is respectfully requested that a Certificate of Correction be issued to correct the front page of the patent, specifically, the assignee information as shown on the attached form PTO-1050.

It is respectfully requested that the assignee information be corrected.

The assignee information is listed as Hitachi, Ltd. and High-Electronics Corporation. The assignee information should be listed as Hitachi, Ltd. and Hitachi High Technologies Corporation.

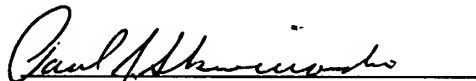
In view of the foregoing, granting of the present request for Certificate of Correction is respectfully requested.

JUN 26 2007

If any fees become due in connection with the filing of this Request, including fees due under 37 CFR 1.323, please charge such fees to the deposit account of Antonelli, Terry, Stout & Kraus, Deposit Account No. 01-2135 (Case: 520.41064X00).

Respectfully submitted,

ANTONELLI, TERRY, STOUT & KRAUS, LLP


Paul J. Skwierawski
Registration No. 32,173

PJS/ayy
(703) 312-6600
Attachment

JUN 26 2007

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number. (Also Form P10-1050)

UNITED STATES PATENT AND TRADEMARK OFFICE**CERTIFICATE OF CORRECTION**

PATENT NO: 7,187,438

DATED: March 6, 2007

INVENTOR(S): HAMAMATSU, et al.

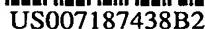
it is certified that an error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

(73) Assignees: Hitachi, Ltd., Tokyo (JP) and Hitachi High Technologies Corporation, Tokyo (JP)

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PATENT NO. 7,187,438
No. of additional copies

JUN 26 2007



(10) **Patent No.:** US 7,187,438 B2
(45) **Date of Patent:** Mar. 6, 2007

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- Primary Examiner—Michael P. Stafira*

- (74) *Attorney, Agent, or Firm*—Antonelli, Terry, Stout and Kraus, LLP.

- (57) **ABSTRACT**

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- The present invention is characterized by the following: incident illumination and oblique illumination are performed on a scratch and a foreign material, which have been made on a surface of a polished or a ground insulating layer, with substantially the same luminous flux; and on the basis of a correlation such as a ratio of intensity of scattered light generated by the shallow scratch and the foreign material between the incident illumination and the oblique illumination, the shallow scratch is discriminated from the foreign material.

- The present invention is characterized by the following: incident illumination and oblique illumination are performed on a scratch and a foreign material, which have been made on a surface of a polished or a ground insulating layer, with substantially the same luminous flux; and on the basis of a correlation such as a ratio of intensity of scattered light generated by the shallow scratch and the foreign material between the incident illumination and the oblique illumination, the shallow scratch is discriminated from the foreign material.

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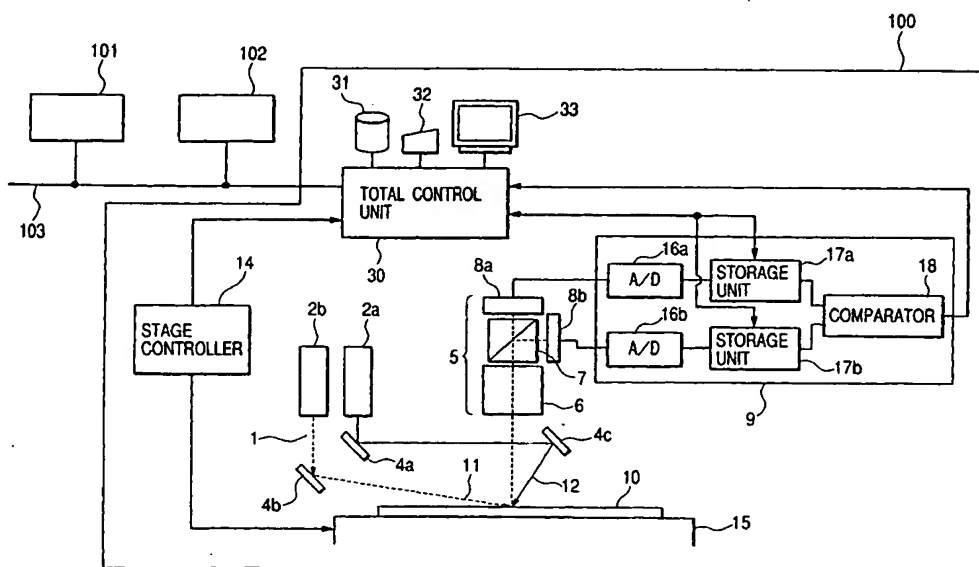
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